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(54) Title: FORMATION OF A LITHIUM COMPRISING STRUCTURE ON A SUBSTRATE BY ALD

(57) Abstract: The present invention discloses a method for the formation of lithium comprising layer on a substrate using an atomic layer deposition method. The method comprises the sequential pulsing of a lithium precursor through a reaction chamber for deposition upon a substrate. Using further oxidising pulses and or other metal containing precursor pulses, an electrolyte suitable for use in thin film batteries may be manufactured.